



LSI:Adds the Lapis Miyagi as a newly manufacturing site for 0.18um memory products as a part of BCP

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7. Summary

14th July 2020
ROHM Co., Ltd.

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1 . Summary of the change



1-1) Purpose of change

- Establish multiple manufacturing resources for the stabilized product supply by transferring some products from Rohm Kyoto to LAPIS Miyagi factory.

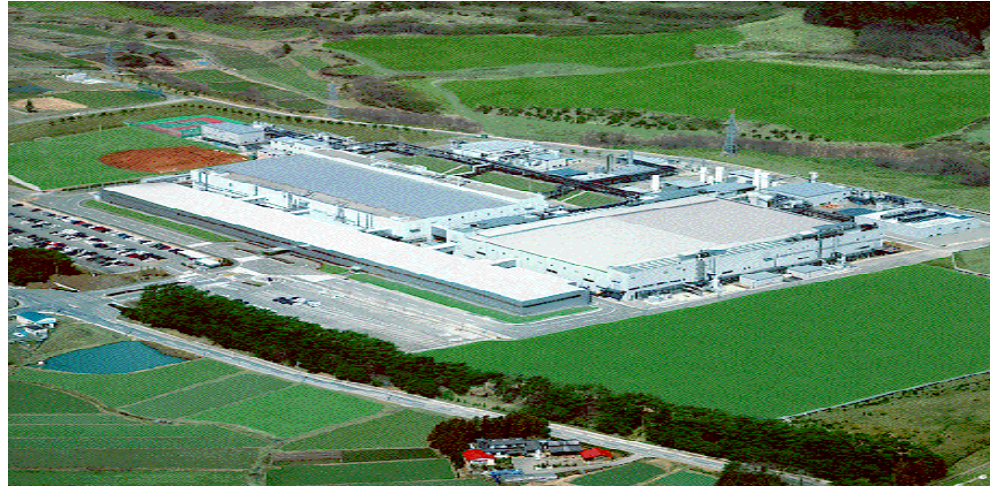
1-2) Contents of change

- Add Lapis Miyagi factory for application of 0.18um memory product of the wafer process producing. The quality characteristics are guaranteed by LAPIS Miyagi, which has produced products from 2013 in the same line as that of Rohm Kyoto.
(There is not a change about the assembly factory after the wafer process shipment)

1-3) Schedule of change

- We plan to change it immediately after your approval acquisition, because LAPIS Miyagi factory has mass-produced from 2013.
It becomes the intensive production in LAPIS Miyagi after approval from the viewpoint of production efficiency.

2. Summary of LAPIS Miyagi factory



2-1) LAPIS Miyagi factory summary

Company name : LAPIS Semiconductor Miyagi Co., Ltd.

Location : 1, Okinodaira Ohira-mura Kurokawa-gun, Miyagi

Establishment : 8/4/1988

Representative : Naotaka Fujita (President)

Production item : Monolithic IC (LSI)

Production Capacity : LSI 25,000~35,000 wafers(200mm)/ a month

Employee : 229

2-2) LSI 0.18 μ m PRODUCTION RESULTS

(Transferred products of the wafer process producing in Rohm Kyoto factory to LAPIS Miyagi factory)

START OF PRODUCTION : Dec. 2013

PRODUCTION VOLUME : 79,000wafers

Smallest Design Rule : 0.13 μ m

2. Summary of LAPIS Miyagi factory

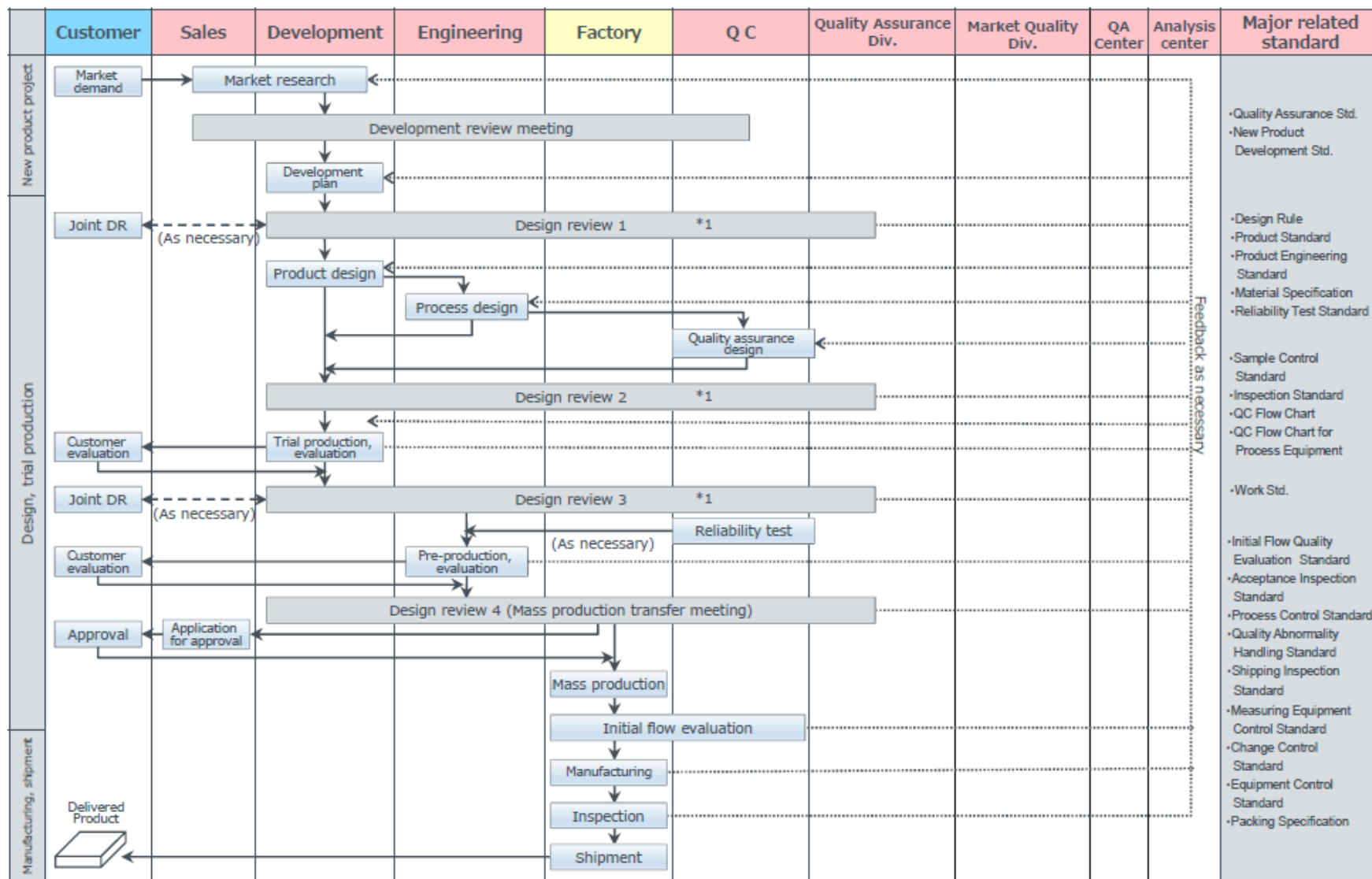


2-3) Environmental management (clean room)

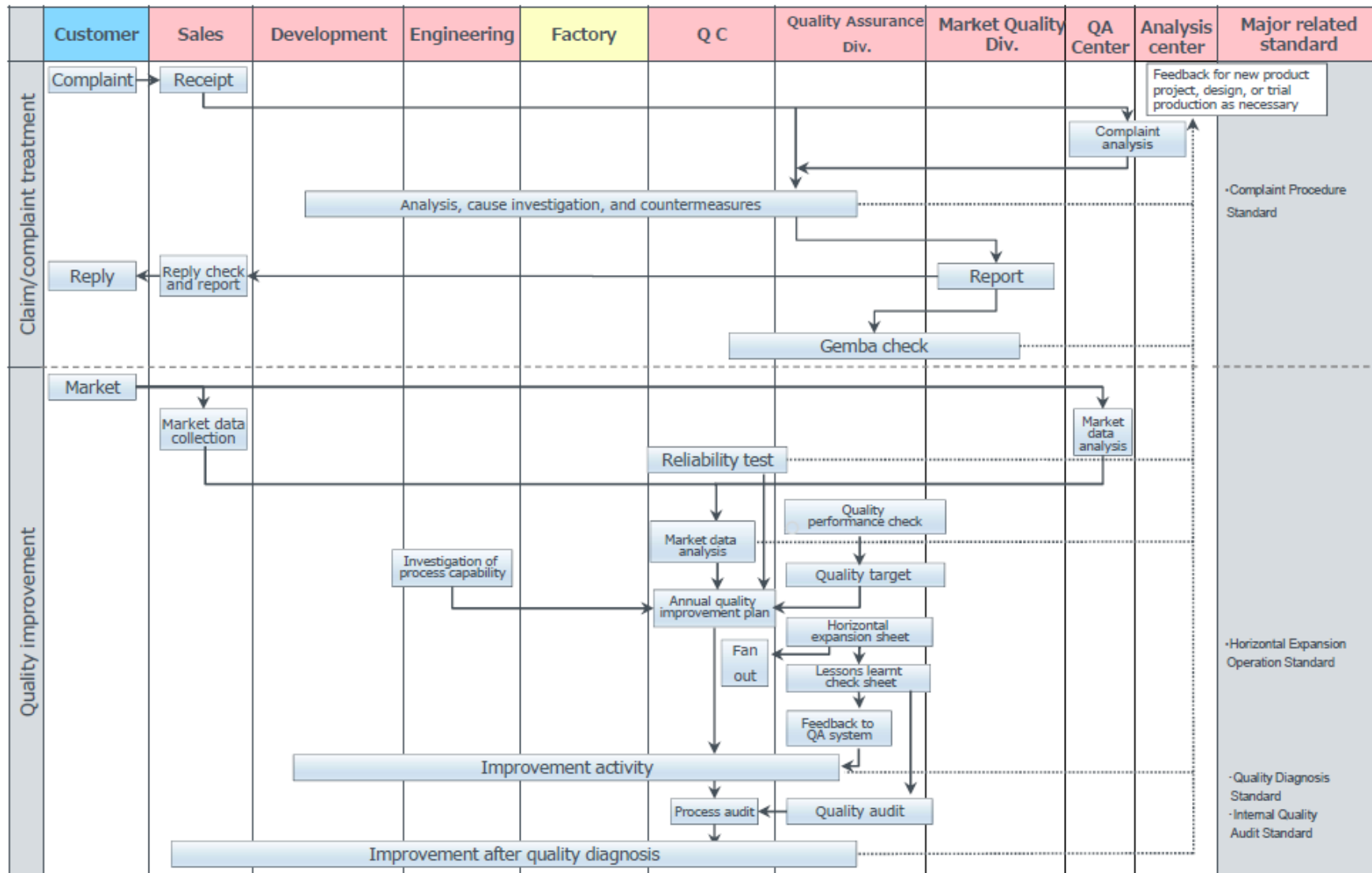
| ITEM | | FREQUENCY | METHOD | UNIT | Management Value | Rohm Kyoto (Existing) | LAPIS Miyagi (New) |
|---------------------------|----------------|-----------------------|-------------------------------|--------|------------------|-----------------------|--------------------|
| Temperature | | Continuous Monitoring | Thermometer | ℃ | 23±1 | 22～24 | 22～24 |
| Humidity | | Continuous Monitoring | Hygrometer | % | 45±10 | 40～50 | 40～50 |
| Cleanlines s | Passage Area | Continuous Monitoring | Measure by Laser Dust Counter | pcs/cf | 35 (0.1um) | Less than 10 | Less than 10 |
| | Operation Area | Continuous Monitoring | | pcs/cf | 35 (0.1um) | Less than 10 | Less than 10 |
| | MASK Area | Continuous Monitoring | | pcs/cf | 35 (0.1um) | Less than 10 | Less than 10 |
| Smallest Design Rule (um) | | | | | | 0.13 | 0.13 |

There is no difference about the environmental management (clean room) between the factories.

3. Quality assurance system(1/2)



3 . Quality assurance system(2/2)



There is no change about Quality assurance System

4. Change point of 5M with the factory transferring



| 5M | | Rohm Kyoto | LAPIS Miyagi | Comparison |
|-------------|-------------------------------------|---|-----------------------------|--------------|
| Man | - | The worker who was authorized in a license system in the company operate according to operating procedures. | | Equal |
| Machine | Equipment in use | Existing device (the same method) | | Equal |
| | Factory management contents | Conforming to QC chart. | | Equal |
| | Management method | In accordance with facilities QC chart, carrying out SPC management. | | Equal |
| | Transport between equipments | Cart / Robot Cart | OHV(Overhead Hoist Vehicle) | Different ※1 |
| Materials | Wafer | 200mm Si wafers | | Equal |
| | Others | same thing is used by centralized supply system. | | Equal |
| Method | Processing condition | Conforming to QC chart. | | Equal |
| | Treatment of the control limits out | Conforming to quality abnormality measures rule. | | Equal |
| | Inspection contents | Conforming to inspection standard. | | Equal |
| Measurement | Measuring equipment ※2 | Although there is difference in the device by the wafer diameter, equipment is calibrated in equal standard such as precision and repeatability . | | Equal |
| | Management method | Conforming to measure administrative provision. | | Equal |

※1 About the Transport between equipments, Rohm Kyoto line uses a cart or automatic robot cart but LAPIS Miyagi line uses OHV(Overhead Hoist Vehicle).

And the wafer storing container is changed to FOUP (Front Opening Unified Pod) from BOX type.

The tolerance for the floating dust greatly improves.

※2 The measuring equipment refers to the equipment of the film thickness, Electric characteristic, Dimensions, Resistivity, Reflectance, Refractive index and Particle.

5. Investigation for the change point of 5M (process)



5-1) Target process

| Process | | Existing | New |
|------------------|--|-------------------|---------------------|
| Wafer Process | STI GATE Metalization Passivation | Rohm Kyoto | LAPIS Miyagi |
| Assembly Process | Wafer Probe Test Dicing Assy | No Change | |
| Test Process | Final Test | No Change | |

It is only wafer process to perform change application this time.
Assembly and Test process does not have the change.

5. Investigation for the change point of 5M (process)



5-2) Process capability of primary characteristics of main process

We compared the process capability of Rohm Kyoto with LAPIS Miyagi referring to primary characteristic of main processes.
it has more than Cpk1.66 and does not have any problem.

| | Rohm Kyoto | | | LAPIS Miyagi | | |
|----------------------------|------------|------|------|--------------|------|------|
| Item | σ | Cp | Cpk | σ | Cp | Cpk |
| GATE Oxide Thickness | 2.53 | 2.63 | 2.14 | 3.23 | 2.06 | 1.81 |
| GATE POLY size | 0.006 | 1.73 | 1.68 | 0.005 | 2.14 | 1.93 |
| CONT size | 0.004 | 2.21 | 2.03 | 0.003 | 2.50 | 2.14 |
| 1 st Metal size | 0.004 | 2.02 | 1.77 | 0.004 | 2.20 | 2.18 |

n=20Lot each
25point/Lot

5. Investigation for the change point of 5M (process)



5-3) Process capability of main element properties

We compared the process capability of Rohm Kyoto with LAPIS Miyagi referring to characteristic of main elements.

it has more than Cpk1.66 and does not have any problem.

| | Rohm Kyoto | | | LAPIS Miyagi | | |
|-------------|------------|------|------|--------------|------|------|
| Item | σ | Cp | Cpk | σ | Cp | Cpk |
| NMOS Vth | 0.02 | 1.86 | 1.81 | 0.02 | 1.82 | 1.74 |
| PMOS Vth | 0.02 | 1.86 | 1.79 | 0.02 | 1.96 | 1.72 |
| Memory 1Vth | 0.27 | 2.08 | 2.01 | 0.27 | 2.03 | 1.92 |
| Memory 0Vth | 0.27 | 1.82 | 1.79 | 0.22 | 2.25 | 2.25 |
| CONT CR | 0.60 | 2.22 | 2.11 | 0.33 | 4.02 | 3.78 |
| VIA CR | 0.40 | 2.07 | 2.04 | 0.44 | 1.88 | 1.86 |

n=20Lot each
25point/Lot

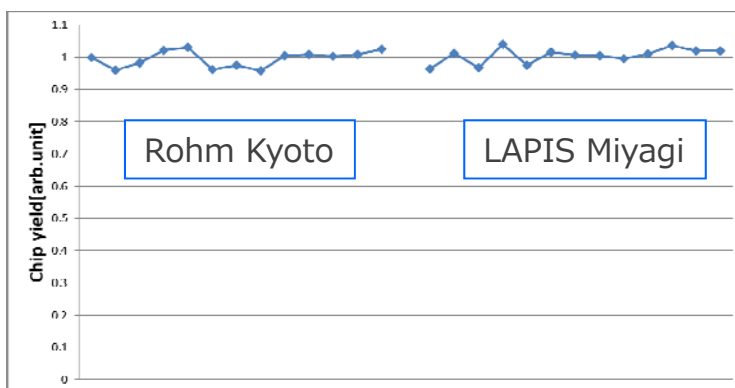
5. Investigation for the change point of 5M (process)



5-4) CHIP Yield(WA measurement)

We compared the CHIP yield of Rohm Kyoto product with LAPIS Miyagi product.

There is no difference in CHIP yield of both lines on a monthly basis for the most recent year.



5-5) Reliability evaluation result of the wafer level

We show the reliability evaluation result of the wafer level at 0.18um memory line as follows.

All tests satisfy a criterion and do not have any problem.

| Test Item | Test symbol | Evaluation Criteria | | | | Results judgment |
|-------------------|-------------|-----------------------------|-------------|-----------------|---------|------------------|
| | | judgment | Temperature | Voltage/Current | life | |
| Gate oxide film | TDDDB | 0.1%defective rate | 150℃ | Vccmax:5.5V | 20years | Pass |
| Slow trap | NBTI | $\Delta I_{dsat} \geq 10\%$ | 25℃ | Vccmax:5.5V | 20years | Pass |
| Hot carrier | HCI | $\Delta I_{dsat} \geq 10\%$ | 150℃ | Vccmax:5.5V | 20years | Pass |
| Stress migration | SM | $\Delta R \geq 10\%$ | 150℃ | - | 20years | Pass |
| Electro migration | EM | $\Delta R \geq 10\%$ | 150℃ | I=1mA/um | 20years | Pass |

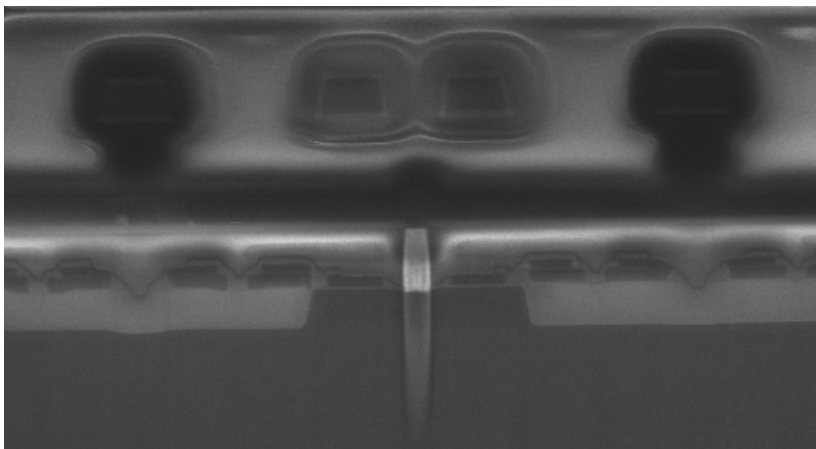
5. Investigation for the change point of 5M (process)



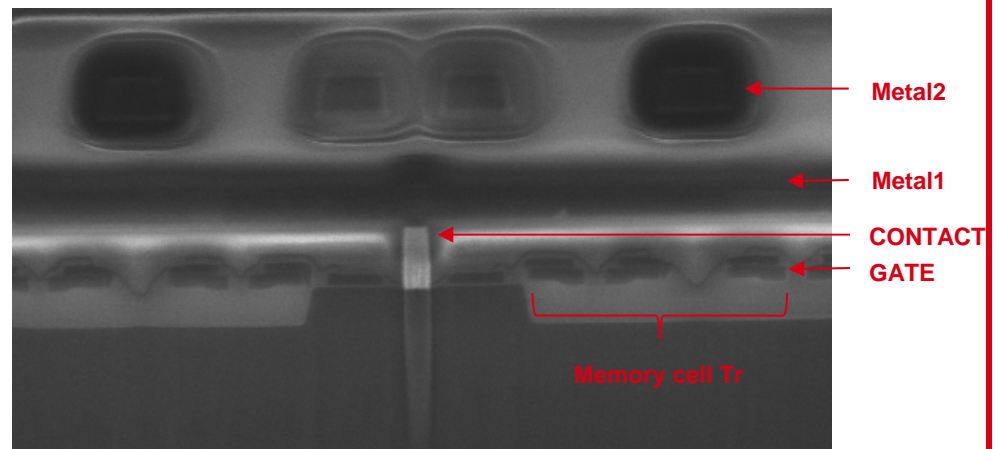
5-6) Cross sectional structure evaluation

The wiring structure of each sample of Rohm Kyoto/LAPIS Miyagi were observed by using FIB. There is not the difference in structure between Rohm Kyoto/LAPIS Miyagi .

Rohm Kyoto



LAPIS Miyagi



6. Investigation for the change point of 5M (product)



6-1) QAT(Quality Approval Test) result

We show the result of the QAT that were executed on the other product at LAPIS Miyagi line, as follows.
All test results satisfy a criterion and do not have any problem.

| Test Item | Test symbol | The number of samples | Evaluation Criteria | Test condition | Test time /cycles | Results judgment |
|-------------------------------|-------------|-----------------------|---|---------------------|-------------------|------------------|
| Pressure Cooker test | PCT | 77pcs×3 | Need to clear the spec of specifications and standard of shipment by the FT measurement after the test. | 121℃/100%RH 2atm | 500h | Pass |
| Temperature cycle test | TCY | 77pcs×3 | | -65℃ ⇔ 150℃ | 1000cyc | Pass |
| High Temperature Storage test | HST | 77pcs×3 | | 150℃ | 2000h | Pass |
| High Acceleration Stress test | HAST | 77pcs×3 | | VDD/130℃/ 85%RH | 200h | Pass |
| Dynamic Burn in test | B/IN | 77pcs×3 | | VDD/150℃ | 2000h | Pass |
| ESD Test (HumanBodyModel) | HBM | 3pcs | Over 2000V | 100pF/1.5kohm | - | Pass |
| ESD Test (Machine Model) | MM | 3pcs | Over 200V | 200pF/0ohm | - | Pass |

7. Summary



From the above evaluation and inspection,
We judge the quality characteristic of the front-end
0.18um memory products in Kyoto is equal
even if the Lapis Miyagi factory is added,
and We have pushed forward product transference.

About the product for your company, we are going to
change it immediately after the approval acquisition.

We would like your confirmation.

